



IP Bridge Exhibit 2016

Silicon VLSI Technology

Fundamentals, Practice and Modeling

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Prentice
Hall

Prentice Hall

Upper Saddle River, NJ 07458

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Library of Congress Cataloging-in-Publication Data

Silicon VLSI technology

p. cm.

ISBN 0-13-085037-3

1. Integrated circuits—Very large scale integration—Design and construction. 2. Silicon. 3. Silicon oxide films. 4. Metal oxide semiconductors. 5. Silicon technology.

TK7874.75.S54 2000

621.39'5—dc21

99-42745

CIP

Publisher: Tom Robbins

Associate Editor: Alice Dworkin

Editorial/Production Supervision: Rose Kernan

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Art Director: Jayne Conte

Cover Design: Bruce Kenselaar

Editorial Assistant: Jesse Power

Copy Editor: Martha Williams

Composition: D&G Limited, LLC



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Upper Saddle River, New Jersey 07458

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Printed in the United States of America

10 9 8 7 6 5 4 3 2 1

ISBN 0-13-085037-3

Prentice Hall International (UK) Limited, *London*

Prentice Hall of Australia Pty. Limited, *Sydney*

Prentice Hall Canada Inc., *Toronto*

Prentice Hall Hispanoamericana, S.A., *Mexico*

Prentice Hall of India Private Limited, *New Delhi*

Prentice Hall of Japan, Inc., *Tokyo*

Pearson Education Pte., Ltd., *Singapore*

Prentice Hall do Brasil Ltda., *Rio de Janeiro*

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7874
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P58
2000
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